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(54) Title: CURABLE COMPOSITION

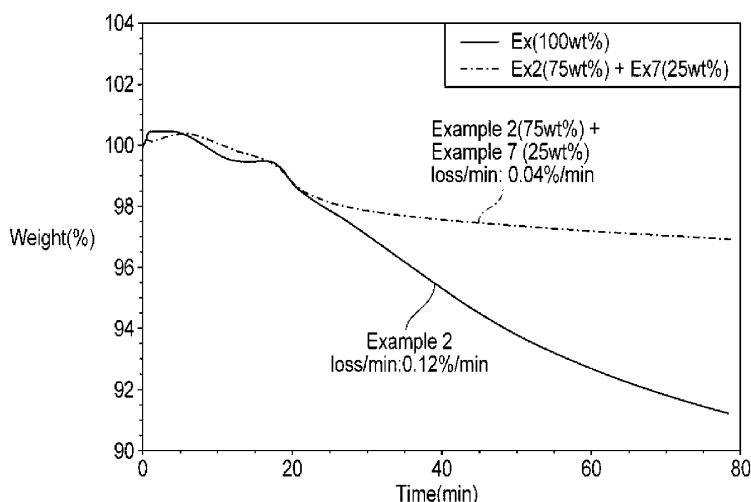


FIG. 1: Comparison of the isothermal baking behavior of Example 2 vs.
a mixture of Example 2 (75wt%) and Example 7 (25wt%).

(57) Abstract: The present invention relates to a curable composition, preferably being a photo-curable composition, comprising at least a 1st monomer compound; a 2nd monomer compound; and a polymerization initiator.

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